

# Electronic and optical properties of atomically scale heterostructure based on MXene and MN (M = Al, Ga): a DFT investigation

Kai Ren<sup>1,\*</sup>, Ruxin Zheng<sup>1</sup>, Peng Xu<sup>1</sup>, Dong Cheng<sup>1</sup>, Wenyi Huo<sup>1</sup>, Jin Yu<sup>2</sup> Zhuoran Zhang<sup>3</sup> and Qingyun Sun<sup>1,\*</sup>

<sup>1</sup>School of Mechanical and Electronic Engineering, Nanjing Forestry University, Nanjing, Jiangsu, China

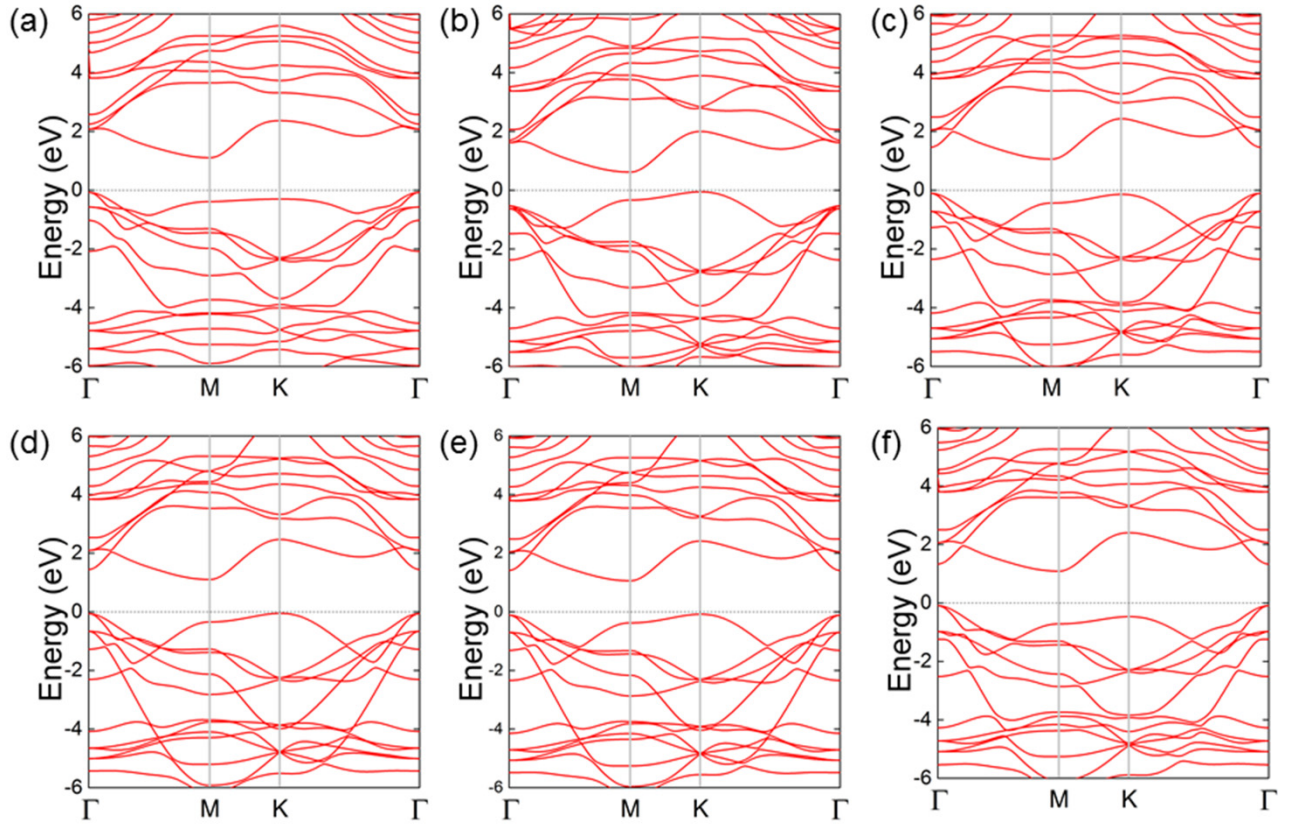
<sup>2</sup>School of Materials Science and Engineering, Southeast University, Nanjing, Jiangsu, China

<sup>3</sup>Center for More-Electric-Aircraft Power System, Nanjing University of Aeronautics and Astronautics, Nanjing 211106, China

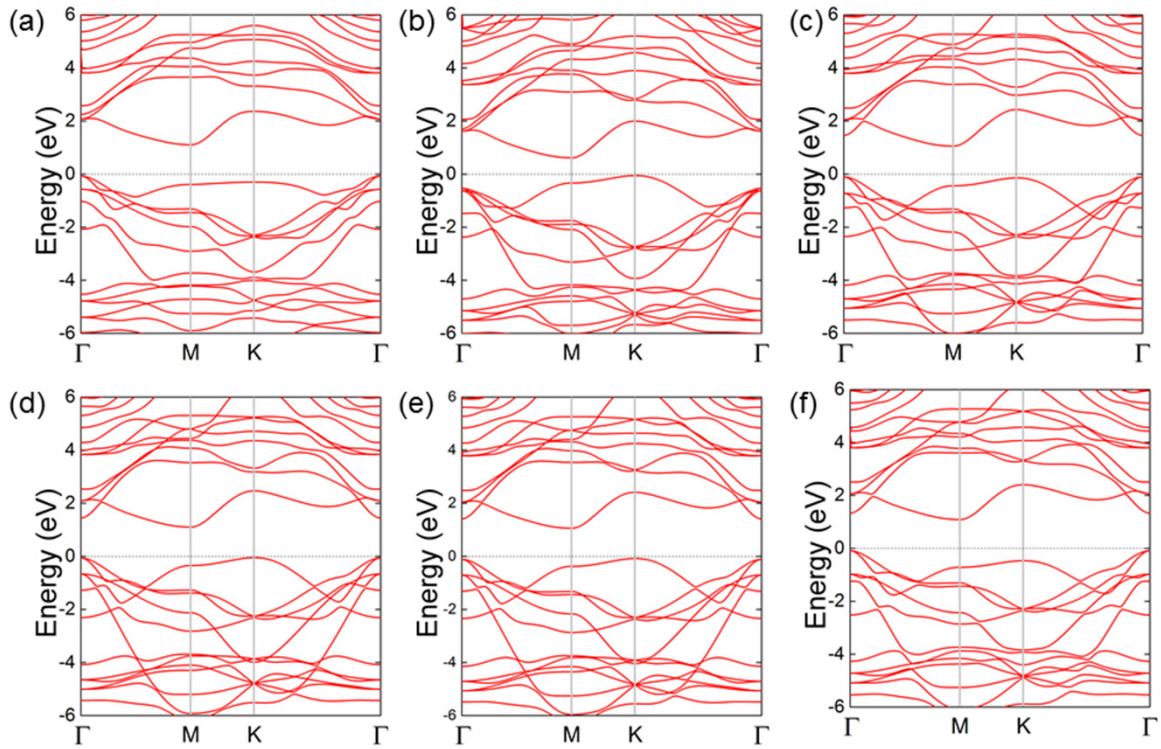
Corresponding author: kairen@njfu.edu.cn (Kai Ren), sunqingyun@njfu.edu.cn (Qingyun Sun)

**Table S1.** The tested results of the energy for the Hf<sub>2</sub>CO<sub>2</sub>/AlN and Hf<sub>2</sub>CO<sub>2</sub>/GaN systems.

<i>k</i> -points	Energy (eV)	
	Hf <sub>2</sub> CO <sub>2</sub> /AlN	Hf <sub>2</sub> CO <sub>2</sub> /GaN
3	-65.455887	-62.773514
4	-65.601831	-62.979732
5	-65.649084	-63.044835
6	-65.664875	-63.066097
7	-65.670985	-63.074063
8	-65.673149	-63.076884
9	-65.673926	-63.077911
10	-65.674286	-63.078323
11	-65.674416	-63.078500
12	-65.674466	-63.078574
13	-65.674520	-63.078633
14	-65.674534	-63.078639
15	-65.674541	-63.078655
16	-65.674545	-63.078670
17	-65.674557	-63.078658

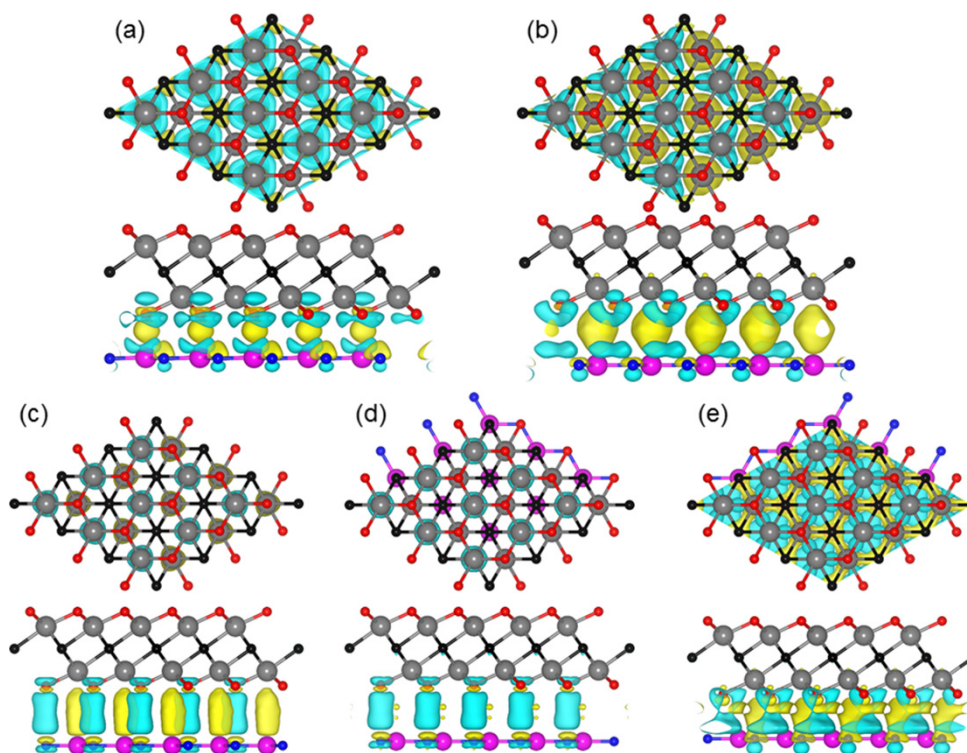


**Figure S1.** The PBE calculated band structure of the (a) AA, (b) AB, (c) AC, (d) AD, (e) AE and (d) AF stacking configurations of the  $\text{Hf}_2\text{CO}_2/\text{AlN}$  vdW heterostructure.

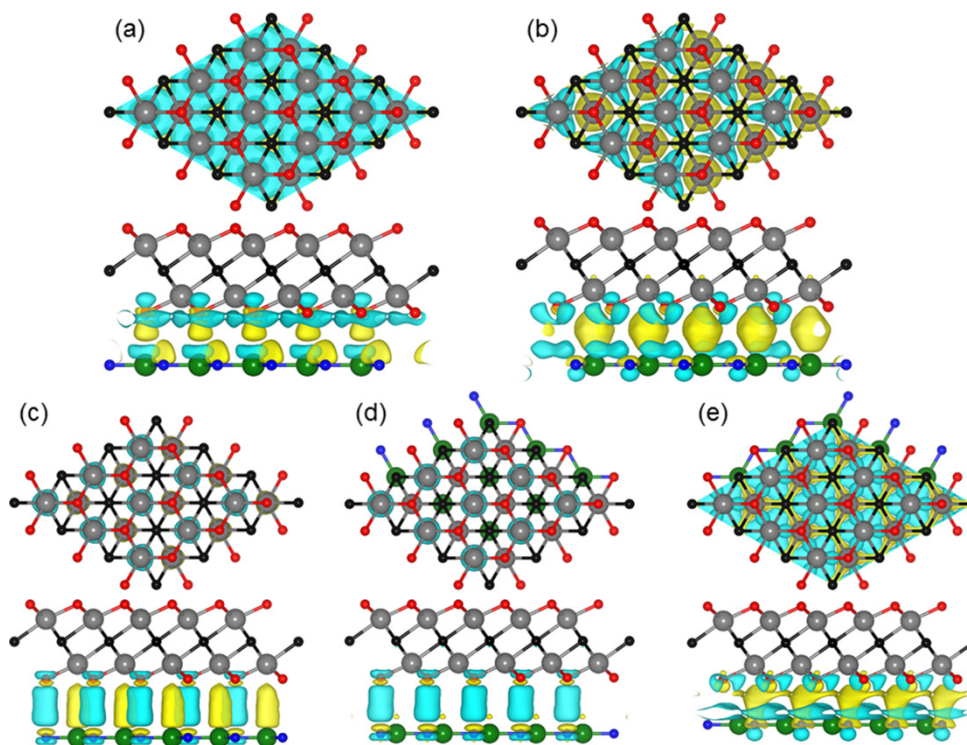


**Figure S2.** The PBE calculated band structure of the (a) AA, (b) AB, (c) AC, (d) AD, (e) AE and (d) AD stacking configurations of the  $\text{Hf}_2\text{CO}_2/\text{AlN}$  vdW heterostructure.

AF stacking configurations of the  $\text{Hf}_2\text{CO}_2/\text{GaN}$  vdW heterostructure.



**Figure S3.** The charge density difference of the (a) AA, (b) AB, (c) AC, (d) AD, (e) AE and (f) AF stacking configurations of the  $\text{Hf}_2\text{CO}_2/\text{AlN}$  vdW heterostructure; the yellow demonstration shows the gaining of the electrons while the cyan one means the losing,  $0.0001 |e|$  is used for the isosurface level.



**Figure S4.** The charge density difference of the (a) AA, (b) AB, (c) AC, (d) AD, (e) AE and (d) AF stacking configurations of the  $\text{Hf}_2\text{CO}_2/\text{GaN}$  vdW heterostructure; the yellow demonstration shows the gaining of the electrons while the cyan one means the losing, 0.0001  $|e|$  is used for the isosurface level.

**Table S2.** The electron transfer (unit:  $|e|$ ) between the interface of the  $\text{Hf}_2\text{CO}_2/\text{AlN}$  and  $\text{Hf}_2\text{CO}_2/\text{GaN}$  vdW heterostructures.

	AA	AB	AC	AD	AE	AF
$\text{Hf}_2\text{CO}_2/\text{AlN}$	0.1513	0.0928	0.0141	0.0082	0.011	0.0296
$\text{Hf}_2\text{CO}_2/\text{GaN}$	0.0414	0.0121	0.0114	0.0076	0.0097	0.0205